T Mumbo	r Hits	Search Text	DB	Time stamp
L Numbe		((438/780) or (438/781) or (438/782) or	USPAT;	2004/05/15 22:32
3	8455		US-PGPUB;	2004,03,13 22.32
		(438/692) or (438/633) or (438/693) or		
l	+	(438/697) or (438/698) or (438/699) or	EPO; JPO;	}
		(438/700) or (438/702) or (438/703)).CCLS.	DERWENT;	1
ŀ			IBM_TDB	
4	289	((cmp or ((chemical adj mechanical) near2	USPAT;	2004/05/15 22:38
1		polish))) near2 ((photoresist or resist))	US-PGPUB;	
	•	poribny, near ((photorox or relative,)	EPO; JPO;	•
		•	DERWENT;	
1	'	•	1	
			IBM_TDB	0004/05/25 00 40
-5	30	(((438/780) or (438/781) or (438/782) or	USPAT;	2004/05/15 22:40
		(438/692) or (438/633) or (438/693) or	US-PGPUB;	
1	1	(438/697) or (438/698) or (438/699) or	EPO; JPO;	.
		(438/700) or (438/702) or (438/703)).CCLS.)	DERWENT;	
		and (((cmp or ((chemical adj mechanical)	IBM TDB	
		near2 polish))) near2 ((photoresist or	_	
		resist)))		
	_		USPAT;	2004/05/15 22:41
6	0	chia-der-chang-hsin-chu.in.		2004/03/13 22:41
			US-PGPUB;	
İ		÷	EPO; JPO;	.
		* '.	DERWENT;	
			IBM_TDB	
. 7	0	hsin-chu-chia-der-chang.in.	USPAT;	2004/05/15 22:42
1		<u> </u>	US-PGPUB;	
l.			EPO; JPO;	
			DERWENT;	-00
			IBM_TDB	.
				2004/05/15 22:42
8	0	chia-der-chang.in.	USPAT;	2004/05/15 22:42
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
9	و	Yi-tung.in.	USPAT:	2004/05/15 22:42
			US-PGPUB;	' '
			EPO; JPO;	
		· · · · · · · · · · · · · · · · · · ·	DERWENT;	!
		·]
	_	(1) (1)	IBM_TDB	2002/05/20 12 47
-	1	("0000424").PN.	USPAT;	2002/05/28 13:47
	·		US-PGPUB;	i
			EPO; JPO;	
			DERWENT;	. 1
		· · · · · · · · · · · · · · · · · · ·	IBM_TDB	
1 -	49798	trench	USPAT;	2002/05/28 13:47
			US-PGPUB;	
1		· ·	EPO; JPO;	
1			DERWENT;	
			IBM TDB	
1	300	twomah and above	USPAT;	2002/05/28 13:48
-	389	trench and shore		2002/05/20 13:48
1 .			US-PGPUB;	[
			EPO; JPO;	
			DERWENT;	
1		•	IBM_TDB	
-	. 4	(trench and shore) and (sti or (shallow adj	USPAT;	2002/05/28 14:29
		trench adj isolation))	US-PGPUB;	
			EPO; JPO;	
+			DERWENT;	
			IBM TDB	,
		(420/600) (007.0	_	2002/11/25 12 44
-	1055	(438/692).CCLS.	USPAT;	2002/11/25 12:44
			US-PGPUB;	1
		<u> </u>	EPO; JPO;	1
1			DERWENT;	
			IBM_TDB	
-	14	((438/692).CCLS.) and (shore or (shore adj	USPAT;	2002/05/28 14:35
1		D))	US-PGPUB;	
			EPO; JPO;	
1			DERWENT;	
	. [
1	· 1	1	IBM TDB	I

-	3	, , , , , , , , , , , , , , , , , , ,	USPAT;	2002/05/28 14:35
-		D))) and (sti or (shallow adj trench adj	US-PGPUB;	
;	1	isolation))	EPO; JPO;	
			DERWENT;	
	114633	(giligen adi (gubatrata en unfer))	IBM_TDB	2002/05/20 15 24
-	114633	(silicon adj (substrate or wafer))	USPAT;	2002/05/28 15:34
			US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
-	127	((silicon adj (substrate or wafer))) and	USPAT:	2002/05/28 15:49
1		(shore or (shore adj d))	US-PGPUB;	2002/03/20 15.45
		(5.1.526 02 (5.1.526 04)	EPO; JPO;	
1			DERWENT;	
1		•	IBM TDB	
-	4	(((silicon adj (substrate or wafer))) and	USPAT;	2002/05/28 15:49
		(shore or (shore adj d))) and trench	US-PGPUB;	
			EPO; JPO;	
		·	DERWENT;	
	1.		IBM TDB	
j	1	("20020160546").PN.	USPAT;	2002/11/25 13:07
			US-PGPUB;	
,			EPO; JPO;	•
		*	DERWENT;	
			IBM_TDB	
-	14734	photo adj resist	USPAT;	2002/11/25 13:15
			US-PGPUB;	i
		·	EPO; JPO;	
			DERWENT;	
	2005	1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1	IBM_TDB	
-	3895	trench adj fill\$2	USPAT;	2002/11/25 13:09
		*	US-PGPUB;	- 1
			EPO; JPO;	
			DERWENT;	
	53493	třench	IBM_TDB USPAT;	2000/11/05/12 00
	33433	Cremon		2002/11/25 13:09
	-		US-PGPUB; EPO; JPO;	
1			DERWENT;	
			IBM TDB	-0.0
-	22142	стр	USPAT;	2002/11/25.13:10
			US-PGPUB;	2002/11/25:15:10
			EPO; JPO;	
		,	DERWENT;	·
		2 * *	IBM TDB	
_	23096	planariz\$3	USPAT;	2002/11/25 13:10
		•	US-PGPUB;	. ,
		· · · · · · · · · · · · · · · · · · ·	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	138	(photo adj resist) and (trench adj fill\$2)	USPAT;	2002/11/25 13:10
			US-PGPUB;	
			EPO; JPO;	
1			DERWENT;	
		(//-N-h	IBM_TDB	
-	61	((photo adj resist) and (trench adj fill\$2))	USPAT;	2002/11/25 13:10
		and cmp	US-PGPUB;	
		*	EPO; JPO;	
	.		DERWENT;	
_	47	(((photo add regist) and (transh add	IBM_TDB	2002/11/25
1	"/	(((photo adj resist) and (trench adj fill\$2)) and cmp) and planariz\$3	USPAT;	2002/11/25 13:10
		rrrryz// and cmp / and pranarizss	US-PGPUB;	[.
			EPO; JPO;	
1	1		DERWENT;	
_	266601	resist	IBM_TDB USPAT;	2002/11/25 12 15
!	200001		US-PGPUB;	2002/11/25 13:15
1	<u> </u>		EPO; JPO;	
1		•	DERWENT;	, [
	[IBM TDB	, [
		The state of the s		L

•					
-		14734	(photo adj resist) and resist	USPAT;	2002/11/25 13:16
			· .	US-PGPUB;	
				EPO; JPO;	,
		,		DERWENT;	
		956	(trough add fill(2) and regist	IBM_TDB	2002/11/25 12:16
-		856	(trench adj fill\$2) and resist	USPAT;	2002/11/25 13:16
			*	US-PGPUB; EPO; JPO;	-
		1	·	DERWENT;	
				IBM TDB	
_		351	cmp and ((trench adj fill\$2) and resist)	USPAT;	2002/11/25 13:16
		332	omp and ((cronon adj rrrry), and represe,	US-PGPUB;	2002/11/23 13:10
1				EPO; JPO;	**,
		•		DERWENT;	
	٠.			IBM TDB	
-		254	(cmp and ((trench adj fill\$2) and resist))	USPAT;	2002/11/25 13:17
		Ì	and planariz\$3	US-PGPUB;	
				EPO; JPO;	
				DERWENT;	- 0
	•			IBM_TDB	:
-		2		USPAT	2002/11/25 13:39
-		1		USPAT	2002/11/25 13:39
-		2969		USPAT;	2003/11/05 13:53
			(438/692) or (438/633)).CCLS.	US-PGPUB	
-		200436	resist or (photo near2 resist)	USPAT;	2003/07/09 13:35
			(1/420/000) (200/000)	US-PGPUB	2000 10 = 1 = 2
-		838	(((438/780) or (438/781) or (438/782) or	USPAT;	2003/07/09 13:34
			(438/692) or (438/633)).CCLS.) and (resist	US-PGPUB	
1		24655	or (photo near2 resist)) ((resist or (photo near2 resist)) near .	HCDATE	2002/07/22 12 25
-		24655		USPAT;	2003/07/09 13:35
		354	(layer or film))	US-PGPUB	2002/07/20 14 46
-		. 354	(((resist or (photo near2 resist)) near (layer or film))) and (((438/780) or	USPAT; US-PGPUB	2003/07/09:14:46
1			(438/781) or (438/782) or (438/692) or	US-PGPUB	
		,	(438/633)).CCLS.)		*
_		1		USPAT	2003/07/09 14:38
_		_	("5607880" "5747381" "5783482"	USPAT	2003/07/09 14:38
			"5948700" "6030706" "6030892").PN.	001111	2003/07/05 11.30
-		1373	((438/424) or (438/427) or (438/443)).CCLS.	USPAT;	2003/07/09 14:46
				US-PGPUB	
-		23154	(cmp or ((chemical adj mechanical) near2	USPAT;	2003/10/23 16:31
			polish))	US-PGPUB	
-		717	(((438/424) or (438/427) or	USPAT;	2003/07/09 14:47
١.			(438/443)).CCLS.) and ((cmp or ((chemical	US-PGPUB	
			adj mechanical) near2 polish)))		•
-		78		USPAT;	2003/07/09 15:59
			(438/443)).CCLS.) and ((cmp or ((chemical	US-PGPUB	
			adj mechanical) near2 polish)))) and	•	,
			(((resist or (photo near2 resist)) near		
		71740	(layer or film)))		0000/00/00 == ==
-		71742	dish or dishing	USPAT;	2003/07/09 15:59
<u>.</u>		443	(dish or dishing) and (((429/790)) or	US-PGPUB	2002/07/20 16 25
~		443	(dish or dishing) and (((438/780) or (438/781) or (438/782) or (438/692) or	USPAT;	2003/07/09 16:05
		ē	(438/633)).CCLS.)	US-PGPUB	
_		О	6436833.URPN.	USPAT	2003/07/09 16:28
-		6	("5173439" "5721173" "5880007"	USPAT	2003/07/09 16:28
			"6001706" "6048775" "6107159").PN.	ODERI	2003/07/09 10:28
-		4	6171962.URPN.	USPAT	2003/07/09 16:45
-		5	("4613888" "5094972" "5298110"	USPAT	2003/07/09 16:45
			"5702977" "5817567").PN.		
· -		138	((((438/424) or (438/427) or	USPAT;	2003/07/09 16:52
		- '	(438/443)).CCLS.) and ((cmp or ((chemical	US-PGPUB	10.52
i			adj mechanical) near2 polish)))) and (dish		•
1			or dishing)		
-		3875	((438/780) or (438/781) or (438/782) or	USPAT;	2003/10/23 16:34
			(438/692) or (438/633)).CCLS.	US-PGPUB;	
			•	EPO; JPO;	
		·		DERWENT;	
L				IBM TDB	

•		•		
-	50475	(rie or (reactive near2 ion))	USPAT; US-PGPUB;	2003/10/23 16:30
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
- '	32793	(cmp or ((chemical adj mechanical) near2	USPAT; US-PGPUB;	2003/10/23 17:10
		polish))	EPO; JPO;	,
'	ū.		DERWENT;	
			IBM_TDB	
-	1901	((rie or (reactive near2 ion))) same ((cmp or ((chemical adj mechanical) near2	USPAT; US-PGPUB;	2003/10/23 16:31
		polish)))	EPO; JPO;	
,			DERWENT;	
		(((((((((((((((((((((((((((((((((((((((IBM_TDB	0000 /10 /00 16 01
-	156	(((438/780) or (438/781) or (438/782) or (438/692) or (438/633)).CCLS.) and (((rie or	USPAT; US-PGPUB;	2003/10/23 16:31
		(reactive near2 ion))) same ((cmp or	EPO; JPO;	
		((chemical adj mechanical) near2 polish))))	DERWENT;	
	7062	//420/700) on /420/701) on /420/700) on	IBM_TDB	2004/05/15 22 22
<u> </u>	7962	((438/780) or (438/781) or (438/782) or (438/692) or (438/633) or (438/693) or	USPAT; US-PGPUB;	2004/05/15 22:32
		(438/697) or (438/698) or (438/699) or	EPO; JPO;	
	- 22	(438/700) or (438/702) or (438/703)).CCLS.	DERWENT;	
	12015	(photoresist or resist) and (cmp or	IBM_TDB	2002/10/22 17:11
,	12015	(chemical adj mechanical adj planarize))	USPAT; US-PGPUB;	2003/10/23 17:11
-		,	EPO; JPO;	
			DERWENT;	
1_	1202	(((438/780) or (438/781) or (438/782) or	IBM_TDB · USPAT;	2003/10/23.16:48
	. 1202	(438/692) or (438/633) or (438/693) or	US-PGPUB;	2003/10/23.10:48
		(438/697) or (438/698) or (438/699) or	EPO; JPO;	.*
		(438/700) or (438/702) or (438/703)).CCLS.)	DERWENT;	
		and ((photoresist or resist) and (cmp or (chemical adj mechanical adj planarize)))	IBM_TDB	* .
-	129	((((438/780) or (438/781) or (438/782) or	USPAT;	2003/10/23 17:09
1		(438/692) or (438/633) or (438/693) or	US-PGPUB;	
		(438/697) or (438/698) or (438/699) or (438/700) or (438/702) or (438/703)).CCLS.)	EPO; JPO;	·
1		and ((photoresist or resist) and (cmp or	DERWENT; IBM TDB	, ,
		(chemical adj mechanical adj planarize))))		
		and (((rie or (reactive near2 ion))) same		
		((cmp or ((chemical adj mechanical) near2 polish))))	·	
- `	1377	1 •	USPAT;	2003/10/23 17:05
		or ((chemical adj mechanical) near2	US-PGPUB;	
		polish)))) and ((photoresist or resist) and (cmp or (chemical adj mechanical adj	EPO; JPO; DERWENT;	. ,
		temp of tenemical adj mechanical adj	IBM TDB	
-	129	((((rie or (reactive near2 ion))) same ((cmp	USPAT;	2003/10/23 17:05
		or ((chemical adj mechanical) near2 polish)))) and ((photoresist or resist) and	US-PGPUB;	0
	-	(cmp or (chemical adj mechanical adj	EPO; JPO; DERWENT;	,
	*	planarize)))) and (((438/780) or (438/781)	IBM_TDB	
		or (438/782) or (438/692) or (438/633) or		
		(438/693) or (438/697) or (438/698) or (438/699) or (438/700) or (438/702) or		
	,	(438/703)).CCLS.)		
-	4048	((cmp or ((chemical adj mechanical) near2	USPAT;	2003/10/23 17:11
		polish))) same (photoresist or resist) and (cmp or (chemical adj mechanical adj	US-PGPUB; EPO; JPO;	
		planarize))	DERWENT;	
		, -	IBM_TDB	
-	4143	((cmp or ((chemical adj mechanical) near2	USPAT;	2003/10/23 17:11
		<pre>polish))) same (photoresist or resist)</pre>	US-PGPUB; EPO; JPO;	
			DERWENT;	
L		•	IBM_TDB	

				<u>.</u>
-	419832	(photoresist or resist)	USPAT;	2003/10/23 17:11
		· ·	US-PGPUB;	
			EPO; JPO;	•
		,	DERWENT;	
			IBM_TDB	· .
-	4143	((cmp or ((chemical adj mechanical) near2	USPAT;	2003/10/23 17:12
1		polish))) same ((photoresist or resist))	US-PGPUB;	
1			EPO; JPO;	4
			DERWENT;	
1	-80	•	IBM TDB	
	1296	((cmp or ((chemical adj mechanical) near2	USPĀT;	2003/10/23 17:12
		polish))) with ((photoresist or resist))	US-PGPUB;	
	•	1	EPO; JPO;	·
i .			DERWENT;	
		•	IBM TDB	
_	451	(((cmp or ((chemical adj mechanical) near2	USPAT;	2003/10/23 17:12
		polish))) with ((photoresist or resist)))	US-PGPUB;	
		and ((rie or (reactive near2 ion)))	EPO; JPO;	*
1			DERWENT;	
		*	IBM TDB	
i -	55	(((438/780) or (438/781) or (438/782) or	USPAT;	2003/10/23 17:15
		(438/692) or (438/633) or (438/693) or	US-PGPUB;	= 0.00, = 0, 20
	1	(438/697) or (438/698) or (438/699) or	EPO; JPO;	.
		(438/700) or (438/702) or (438/703)).CCLS.)	DERWENT;	, ,
		and ((((cmp or ((chemical adj/mechanical))	IBM_TDB	
· .		near2 polish))) with ((photoresist or	1211_122	
		resist))) and ((rie or (reactive near2		·
	1	ion))))	•	
	624		IICDAT.	2002/10/22 17-17
- .	624	or ((chemical adj mechanical) near2	USPAT; US-PGPUB;	2003/10/23 17:17
į.		polish)))) same ((photoresist or resist))	EPO; JPO;	
			DERWENT;	
		(((()))	IBM_TDB	5000 (70 (00) 75 44
_	. 42	1 1111	USPAT;	2003/10/23/17:44
		or ((chemical adj mechanical) near2	US-PGPUB;	
		polish)))) same ((photoresist or resist)))	EPO; JPO;	
		and (((438/780) or (438/781) or (438/782) or	DERWENT;	
-		(438/692) or (438/633) or (438/693) or	IBM_TDB	9
		(438/697) or (438/698) or (438/699) or		·
	244	(438/700) or (438/702) or (438/703)).CCLS.)		0001105155
-	244		USPAT;	2004/05/15 22:37
	_	polish))) near2 ((photoresist or resist))	US-PGPUB;	
			EPO; JPO;	
	·		DERWENT;	·
		///	IBM_TDB	0000/10/05 55
1	28	(((cmp or ((chemical adj mechanical) near2	USPAT;	2003/10/23 17:44
	0	polish))) near2 ((photoresist or resist)))	US-PGPUB;	·
1	1	and (((438/780) or (438/781) or (438/782) or	EPO; JPO;	
		(438/692) or (438/633) or (438/693) or	DERWENT;	
1.		(438/697) or (438/698) or (438/699) or	IBM_TDB	
1	_	(438/700) or (438/702) or (438/703)).CCLS.)		0000/10/5
- 4	1	("6613690").PN.	USPAT;	2003/10/24 11:44
			US-PGPUB;	'
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	0	6613690.URPN.	USPAT	2003/10/24 11:44
-	8	("4385975" "5065273" "5077234"	USPAT	2003/10/24 11:44
		"5100823" "5723374" "5759262"		
		"6130126" "6420226").PN.		
_	. 2	6420226.URPN.	USPAT	2003/10/24 11:54
-	9	1	USPAT	2003/10/24 11:54
		"6013547" "6080638" "6130470"		
		"6150686" "6174764" "6340623").PN.		
-	7620	((438/780) or (438/781) or (438/782) or	USPAT;	2003/11/05 13:57
		(438/692) or (438/626) or (438/631) or	US-PGPUB;	. :-
		(438/633) or (438/693) or (438/725) or	EPO; JPO;	
		(438/697) or (438/699) or (438/760)).CCLS.	DERWENT;	·
	`		IBM_TDB	

			,	
-	39447	cmp or (chemical adj mechanical adj	USPAT;	2003/11/05 13:58
		(polishing or planarizing))	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
		3	IBM_TDB	
-	421221	resist or photoresist	USPAT;	2003/11/05 13:59
		·	US-PGPUB;	
			EPO; JPO;	-
			DERWENT;	1
			IBM_TDB	*
-	19	(((438/780) or (438/781) or (438/782) or	USPAT;	2003/11/05 13:59
		(438/692) or (438/626) or (438/631) or	US-PGPUB;	
		(438/633) or (438/693) or (438/725) or	EPO; JPO;	
		(438/697) or (438/699) or (438/760)).CCLS.)	DERWENT;	
		and ((cmp or (chemical adj mechanical adj	IBM TDB	
		(polishing or planarizing))) near (resist or	. -	
		photoresist))		
- '	157	(cmp or (chemical adj mechanical adj	USPAT;	2003/11/05 14:25
		(polishing or planarizing))) near (resist or	US-PGPUB;	
		photoresist)	EPO; JPO;	
			DERWENT:	
			IBM TDB	
i -	1420928	remove	USPAT;	2003/11/05 14:25
		· ·	US-PGPUB;	
			EPO; JPO;	
i			DERWENT;	
		, ,	IBM TDB	
-	8268	remove near (resist or photoresist)	USPAT;	2003/11/05 14:25
			US-PGPUB;	
			EPO; JPO;	·
			DERWENT;	
	[i		IBM TDB	
_	17	(remove near (resist or photoresist)) with	USPAT;	2003/11/05; 14:25
]	(cmp or (chemical adj mechanical adj	US-PGPUB;	
]	(polishing or planarizing)))	EPO; JPO;	
			DERWENT;	
		,	IBM TDB	+ 10